

L Number	Hits	Search Text	DB	Time stamp
1	3128	(photo\$lsensitive or photo\$lresist or resist) same "0.25"	USPAT	2003/10/31 09:18
2	408	((photo\$lsensitive or photo\$lresist or resist) same "0.25") and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)	USPAT	2003/10/31 12:08
3	204	((((photo\$lsensitive or photo\$lresist or resist) same "0.25") and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine))	USPAT	2003/10/31 09:19
4	198	((((photo\$lsensitive or photo\$lresist or resist) same "0.25") and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and @ay<=2001	USPAT	2003/10/31 09:04
5	55	(((((photo\$lsensitive or photo\$lresist or resist) same "0.25") and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and @ay<=2001) and RF	USPAT	2003/10/31 09:04
6	34526	(photo\$lsensitive or photo\$lresist or resist) with (thick or thickness or micron or angstrom)	USPAT	2003/10/31 09:19
7	2073	((photo\$lsensitive or photo\$lresist or resist) with (thick or thickness or micron or angstrom)) and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)	USPAT	2003/10/31 09:19
8	780	((((photo\$lsensitive or photo\$lresist or resist) with (thick or thickness or micron or angstrom)) and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine))	USPAT	2003/10/31 09:20
9	392	((((photo\$lsensitive or photo\$lresist or resist) with (thick or thickness or micron or angstrom)) and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3)	USPAT	2003/10/31 12:08
10	387	(((((photo\$lsensitive or photo\$lresist or resist) with (thick or thickness or micron or angstrom)) and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3)) and @ay<=2001	USPAT	2003/10/31 09:21
11	79	(((((photo\$lsensitive or photo\$lresist or resist) with (thick or thickness or micron or angstrom)) and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3)) and @ay<=2001) and (RF or (radio adj frequency))	USPAT	2003/10/31 09:41

12	308	((((photo\$lsensitive or photo\$lresist or resist) with (thick or thickness or micron or angstrom)) and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3)) and @ay<=2001) not ((((((photo\$lsensitive or photo\$lresist or resist) with (thick or thickness or micron or angstrom)) and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3)) and @ay<=2001) and (RF or (radio adj frequency))))	USPAT	2003/10/31 09:41
13	305	(((((((photo\$lsensitive or photo\$lresist or resist) with (thick or thickness or micron or angstrom)) and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3)) and @ay<=2001) not ((((((photo\$lsensitive or photo\$lresist or resist) with (thick or thickness or micron or angstrom)) and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3)) and @ay<=2001) and (RF or (radio adj frequency)))) and (etch or etching)	USPAT	2003/10/31 09:47
14	16	("3997367" "5003178" "5468595" "5658469" "5876903" "5962195" "5965461" "5994225" "6103457" "6107172" "6110837" "6174818" "6197687" "6232048" "6319655" "6358670").PN.	USPAT	2003/10/31 09:43
15	244	(((((((photo\$lsensitive or photo\$lresist or resist) with (thick or thickness or micron or angstrom)) and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3)) and @ay<=2001) not ((((((photo\$lsensitive or photo\$lresist or resist) with (thick or thickness or micron or angstrom)) and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3)) and @ay<=2001) and (RF or (radio adj frequency)))) and (etch or etching)) and semiconductor	USPAT	2003/10/31 09:47

16	224	(((((photo\$lsensitive or photo\$iresist or resist) with (thick or thickness or micron or angstrom)) and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3)) and @ay<=2001) not ((((((photo\$lsensitive or photo\$iresist or resist) with (thick or thickness or micron or angstrom)) and (ultra\$lviolet or UV or EUV or DUV) and plasma and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3)) and @ay<=2001) and (RF or (radio adj frequency)))) and (etch or etching)) and semiconductor) and @py<=2002	USPAT	2003/10/31 12:02
17	1	6054254.pn. and (acrylate or alicyclic)	USPAT	2003/10/31 12:06
18	10348	(photo\$iresist or resist) with (implant or implanting or implantation or dope or doping or dopant)	USPAT	2003/10/31 12:07
19	4278	((photo\$iresist or resist) with (implant or implanting or implantation or dope or doping or dopant)) and plasma	USPAT	2003/10/31 12:07
20	4018	((photo\$iresist or resist) with (implant or implanting or implantation or dope or doping or dopant)) and plasma) and (etch or etching)	USPAT	2003/10/31 12:07
21	625	((photo\$iresist or resist) with (implant or implanting or implantation or dope or doping or dopant)) and plasma) and (etch or etching)) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3)	USPAT	2003/10/31 12:08
22	108	((photo\$iresist or resist) with (implant or implanting or implantation or dope or doping or dopant)) and plasma) and (etch or etching)) and ((dope or doping or doped or dopant) same (densify or densification or densifier or harden\$3))	USPAT	2003/10/31 13:16
23	1113	(photo\$iresist or resist) with (acrylate or alicyclic)	USPAT	2003/10/31 13:16
24	2234	"24" and "193 nm"	USPAT	2003/10/31 13:17
25	303	((photo\$iresist or resist) with (acrylate or alicyclic)) and "193 nm"	USPAT	2003/10/31 13:17
26	251	((photo\$iresist or resist) with (acrylate or alicyclic)) and "193 nm") and (lithography or lithograph\$5)	USPAT	2003/10/31 13:17
27	125	((photo\$iresist or resist) with (acrylate or alicyclic)) and "193 nm") and (lithography or lithograph\$5)) and @py<=2001	USPAT	2003/10/31 13:18
-	10720	(photo\$lsensitive or photo\$iresist or resist) and (ultra\$lviolet or UV or EUV or DUV) and plasma	USPAT	2003/10/31 09:01
-	1281	((photo\$lsensitive or photo\$iresist or resist) and (ultra\$lviolet or UV or EUV or DUV) and plasma) and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)	USPAT	2003/10/30 15:32
-	466	((photo\$lsensitive or photo\$iresist or resist) and (ultra\$lviolet or UV or EUV or DUV) and plasma) and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (photo\$lsensitive or photo\$iresist or resist).ab.	USPAT	2003/10/30 15:33

-	252	(((((photo\$lsensitive or photo\$lresist or resist) and (ultra\$lviolet or UV or EUV or DUV) and plasma) and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (photo\$lsensitive or photo\$lresist or resist).ab.) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3))	USPAT	2003/10/30 15:34
-	169	(((((photo\$lsensitive or photo\$lresist or resist) and (ultra\$lviolet or UV or EUV or DUV) and plasma) and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (photo\$lsensitive or photo\$lresist or resist).ab.) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3)) and ((photo\$lsensitive or photo\$lresist or resist) same (CF?sub.4 or fluorine))	USPAT	2003/10/30 15:35
-	169	(((((photo\$lsensitive or photo\$lresist or resist) and (ultra\$lviolet or UV or EUV or DUV) and plasma) and (lithography or lithograph\$)) and (CF?sub.4 or fluorine)) and (photo\$lsensitive or photo\$lresist or resist).ab.) and (shell or cross\$llink\$ or densify or densification or densifier or harden\$3)) and ((photo\$lsensitive or photo\$lresist or resist) same (CF?sub.4 or fluorine)) and @ay<=2001	USPAT	2003/10/30 15:36
-	16	("3997367" "5003178" "5468595" "5658469" "5876903" "5962195" "5965461" "5994225" "6103457" "6107172" "6110837" "6174818" "6197687" "6232048" "6319655" "6358670").PN.	USPAT	2003/10/30 15:37
-	7	("5174856" "5382316" "5534231" "5773201" "5824604" "5970376" "6093655").PN.	USPAT	2003/10/30 16:20